



Future Normal in Semiconductor

2025년 2월 14일(금), 10:55-12:40

Room C(컨벤션홀 L), 5층

D. Thin Film Process Technology 분과

O55_[FC2-D] Atomic Layer Deposition - II

좌장: 최병준 교수(서울과학기술대학교), 문태환 교수(아주대학교)

<p>초청 FC2-D-1 10:55-11:25</p>	<p>Challenges and Advancements in ALD of Chalcogenide Materials for Next-Generation Microelectronics Taeyong Eom Department of Semiconductor System Engineering, Sejong University</p>
<p>FC2-D-2 11:25-11:40</p>	<p>Atomic Layer Deposition of Ge-Sb-Se Ternary Alloy for 3D Vertical Selector-Only Memory Jeongwoo Seo¹, Minu Cho¹, Inkyu Sohn¹, Youngjae Kang², Jong-bong Park², Kiyeon Yang², Wooyoung Yang², and Hyungjun Kim¹ ¹School of Electrical and Electronic Engineering, Yonsei University, ²Device Research Center, SAIT</p>
<p>FC2-D-3 11:40-11:55</p>	<p>Unraveling the Influence of Substrate Surface and Temperature on Microstructural Evolution of Crystalline MoS₂ in Atomic Layer Deposition Seung Ho Ryu^{1,2} and Seong Keun Kim^{1,2} ¹KU-KIST Graduate School of Converging Science and Technology, Korea University, ²Electronic Materials Research Center, KIST</p>
<p>FC2-D-4 11:55-12:10</p>	<p>Atomic Layer Deposition of Low Work Function Metallic Films via Composition Control Using Discrete Feeding ALD Ji Won Han¹, Kyun Seong Dae², Yoon Jeong Kim¹, Ji Sun Heo¹, Woo-Hee Kim¹, Ji-Hoon Ahn¹, Jae Hyuck Jang², Deok-Yong Cho^{3,4}, and Tae Joo Park¹ ¹Department of Materials Science and Chemical Engineering, Hanyang University, ²Center for Research Equipment, KBSI, ³Institute of Photonics, Electronics and Information Technology, Jeonbuk National University, ⁴Department of Physics, Jeonbuk National University</p>
<p>FC2-D-5 12:10-12:25</p>	<p>Atomic Layer Deposition for Molybdenum Interconnects Hyun Jin Lim¹, Sang-Kuk Han¹, Hyo Jin Ahn¹, Young Seo Na², Yeh Been Im¹, Won Jae Choi², and Changhwan Choi^{1,2} ¹Division of Materials Science and Engineering, Hanyang University, ²Department of Semiconductor Engineering, Hanyang University</p>



제 32회 한국반도체학술대회

The 32nd Korean Conference on Semiconductors

2025년 2월 12일(수)-14일(금) | 강원도 하이원리조트

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FC2-D-6 12:25-12:40	Growth of Metallic Ru Thin Film by Oxidant-free Atomic Layer Deposition Below 100 °C 민경민, 이한보람 Department of Materials Science and Engineering, Incheon National University
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